

Refine Search

OP843419

Search Results -

Terms	Documents
L3 and (fluorinated or fluorine or fluorinate)	3

Database:

- US Pre-Grant Publication Full-Text Database
- US Patents Full-Text Database
- US OCR Full-Text Database
- EPO Abstracts Database
- JPO Abstracts Database
- Derwent World Patents Index
- IBM Technical Disclosure Bulletins

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Search History

DATE: Thursday, June 24, 2004 [Printable Copy](#) [Create Case](#)

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result set

DB=USPT; PLUR=YES; OP=ADJ

<u>L9</u>	L3 and (fluorinated or fluorine or fluorinate)	3	<u>L9</u>
<u>L8</u>	L6 and (fluorinated or fluorine or fluorinate)	0	<u>L8</u>
<u>L7</u>	L6 and (fluorinated)	0	<u>L7</u>
<u>L6</u>	L3 and (silicon adj dioxide)	11	<u>L6</u>
<u>L5</u>	L3 and (cyclobutane or polyarylene)	0	<u>L5</u>
<u>L4</u>	L3 and (spin near3 glass)	4	<u>L4</u>
<u>L3</u>	L2 and (anisotropically near2 (etch or etching))	28	<u>L3</u>
<u>L2</u>	L1 and mask	254	<u>L2</u>
<u>L1</u>	fourth adj dielectric	730	<u>L1</u>

END OF SEARCH HISTORY

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Search Results - Record(s) 1 through 3 of 3 returned.

1. Document ID: US 6225207 B1

L9: Entry 1 of 3

File: USPT

May 1, 2001

US-PAT-NO: 6225207

DOCUMENT-IDENTIFIER: US 6225207 B1

TITLE: Techniques for triple and quadruple damascene fabrication

2. Document ID: US 5808855 A

L9: Entry 2 of 3

File: USPT

Sep 15, 1998

US-PAT-NO: 5808855

DOCUMENT-IDENTIFIER: US 5808855 A

TITLE: Stacked container capacitor using chemical mechanical polishing

3. Document ID: US 5627094 A

L9: Entry 3 of 3

File: USPT

May 6, 1997

US-PAT-NO: 5627094

DOCUMENT-IDENTIFIER: US 5627094 A

TITLE: Stacked container capacitor using chemical mechanical polishing

Terms	Documents
L3 and (fluorinated or fluorine or fluorinate)	3

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1. Document ID: US 6225207 B1

L4: Entry 1 of 4

File: USPT

May 1, 2001

US-PAT-NO: 6225207

DOCUMENT-IDENTIFIER: US 6225207 B1

TITLE: Techniques for triple and quadruple damascene fabrication

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	KMC	Draw
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2. Document ID: US 5808855 A

L4: Entry 2 of 4

File: USPT

Sep 15, 1998

US-PAT-NO: 5808855

DOCUMENT-IDENTIFIER: US 5808855 A

TITLE: Stacked container capacitor using chemical mechanical polishing

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	KMC	Draw
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3. Document ID: US 5627094 A

L4: Entry 3 of 4

File: USPT

May 6, 1997

US-PAT-NO: 5627094

DOCUMENT-IDENTIFIER: US 5627094 A

TITLE: Stacked container capacitor using chemical mechanical polishing

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	KMC	Draw
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4. Document ID: US 4696097 A

L4: Entry 4 of 4

File: USPT

Sep 29, 1987

US-PAT-NO: 4696097

DOCUMENT-IDENTIFIER: US 4696097 A

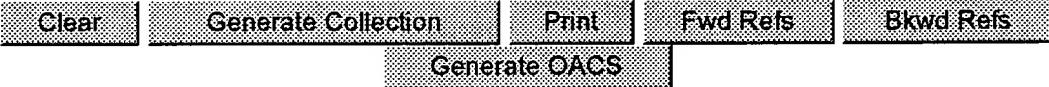
TITLE: Poly-sidewall contact semiconductor device method

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Text](#) | [Image](#) | [Claims](#) | [KMD](#) | [Drawn D](#)[Clear](#)[Generate Collection](#)[Print](#)[Fwd Refs](#)[Bkwd Refs](#)[Generate GACS](#)

Terms	Documents
L3 and (spin near3 glass)	4

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1. Document ID: US 6706608 B2

L6: Entry 1 of 11

File: USPT

Mar 16, 2004

US-PAT-NO: 6706608

DOCUMENT-IDENTIFIER: US 6706608 B2

TITLE: Memory cell capacitors having an over/under configuration



2. Document ID: US 6518670 B1

L6: Entry 2 of 11

File: USPT

Feb 11, 2003

US-PAT-NO: 6518670

DOCUMENT-IDENTIFIER: US 6518670 B1

TITLE: Electrically porous on-chip decoupling/shielding layer



3. Document ID: US 6399480 B1

L6: Entry 3 of 11

File: USPT

Jun 4, 2002

US-PAT-NO: 6399480

DOCUMENT-IDENTIFIER: US 6399480 B1

TITLE: Methods and arrangements for insulating local interconnects for improved alignment tolerance and size reduction



4. Document ID: US 6312966 B1

L6: Entry 4 of 11

File: USPT

Nov 6, 2001

US-PAT-NO: 6312966

DOCUMENT-IDENTIFIER: US 6312966 B1

TITLE: Method of forming sharp tip for field emission display

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5. Document ID: US 6121663 A

L6: Entry 5 of 11

File: USPT

Sep 19, 2000

US-PAT-NO: 6121663

DOCUMENT-IDENTIFIER: US 6121663 A

TITLE: Local interconnects for improved alignment tolerance and size reduction

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6. Document ID: US 6031445 A

L6: Entry 6 of 11

File: USPT

Feb 29, 2000

US-PAT-NO: 6031445

DOCUMENT-IDENTIFIER: US 6031445 A

TITLE: Transformer for integrated circuits

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7. Document ID: US 5930668 A

L6: Entry 7 of 11

File: USPT

Jul 27, 1999

US-PAT-NO: 5930668

DOCUMENT-IDENTIFIER: US 5930668 A

TITLE: Process of fabricating embedded ground plane and shielding structures using sidewall insulators in high frequency circuits having vias

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Text](#) | [Image](#) | [Table](#) | [Claims](#) | [KIN/C](#) | [Drawn D](#)

8. Document ID: US 5386088 A

L6: Entry 8 of 11

File: USPT

Jan 31, 1995

US-PAT-NO: 5386088

DOCUMENT-IDENTIFIER: US 5386088 A

TITLE: Embedded ground plane and shielding structures using sidewall insulators in high frequency circuits having vias

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Text](#) | [Image](#) | [Table](#) | [Claims](#) | [KIN/C](#) | [Drawn D](#)

9. Document ID: US 5285017 A

L6: Entry 9 of 11

File: USPT

Feb 8, 1994

US-PAT-NO: 5285017

DOCUMENT-IDENTIFIER: US 5285017 A

TITLE: Embedded ground plane and shielding structures using sidewall insulators in high frequency circuits having vias

Full	Title	Citation	Front	Review	Classification	Date	Reference				Claims	KUMC	Draw
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10. Document ID: US 4851078 A

L6: Entry 10 of 11

File: USPT

Jul 25, 1989

US-PAT-NO: 4851078

DOCUMENT-IDENTIFIER: US 4851078 A

TITLE: Dielectric isolation process using double wafer bonding

Full	Title	Citation	Front	Review	Classification	Date	Reference				Claims	KUMC	Draw
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Terms	Documents
L3 and (silicon adj dioxide)	11

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□ 11. Document ID: US 4728606 A

L6: Entry 11 of 11

File: USPT

Mar 1, 1988

US-PAT-NO: 4728606

DOCUMENT-IDENTIFIER: US 4728606 A

TITLE: Self-aligned transistor method

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	RUMC	Drawn D
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Terms	Documents
L3 and (silicon adj dioxide)	11

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